

EAST Search History

JRS

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S34	589	((workpiece or semiconductor or substrate or wafer) near5 (coat\$4 or wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat\$4 or etch\$4) near5 (acid or etchant or water or liquid or solution)) and ((vacuum or suck\$4 or suction or evacuat\$4 or exhaust\$4 or aspirat\$4) near5 (acid or etchant or water or liquid or solution) near5 (manifold or nozzle or spout)) and ((manifold or nozzle or applicator or distributor or shower or sprinkl\$4 or spout or flume or spray\$4 or pour\$4) near5 (coating or acid or etchant or water or liquid or solution))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/08/02 09:27